

Attorney Docket No. 071469-0308969
Client Reference: FKL-020

PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of: Noriaki FUKIAGE

Application No.:

Confirmation

No:

Filed: March 30, 2004

Group No.:

Examiner

For: Method of Improving the Wafer to Wafer Uniformity and Defectivity of a Deposited
 Dielectric Film

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

APPLICATION DATA SHEET
37 C.F.R. § 1.76

BIBLIOGRAPHIC DATA

1. Applicant information

First applicant: Noriaki FUKIAGE
Citizenship: JAPAN
Residence: Hartsdale, NY 10530

2. Correspondence information

Correspondence for this application should be addressed as follows:

Customer No.: 00909

3. Application information

Title of Invention: Method of Improving the Wafer to Wafer Uniformity and Defectivity of a
Deposited Dielectric Film

Docket number assigned to this application: 071469-0308969

Suggested Classification: Class:

 Subclass:

 Technology Center to which subject matter is assigned:

Total number of drawing sheets: 10

Type of application: Utility

Application is to be published. Suggested drawing figure for publication:

Secrecy order under § 5.2:

This application does not disclose subject matter of an application which is under a secrecy order pursuant to § 5.2.

4. Representative information

The following have a power of attorney or authorization of agent in this application:

Customer No.: 00909

5. Assignee information

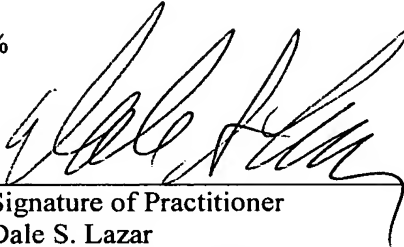
The assignee(s) of this application is/are:

Tokyo Electron Limited
3-6, Akasaka 5-chome, Minato-ku
Tokyo, 107
JAPAN

Extent of interest of assignee in application: 100%

Date: March 30, 2004

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